

ABSTRACT

The aqueous acidic solution for electrolytically depositing high polish, decorative bright, smooth and level copper coatings on large area metal or plastic parts contains a) at least one oxygen-containing, high molecular additive and b) at least one water soluble sulfur compound, wherein the solution additionally contains c) at least one aromatic halogen derivative having the general formula (I), wherein R₁, R₂, R₃, R₄, R₅ and R₆ are each independently radicals selected from the group comprising hydrogen, aldehyde, acetyl, hydroxy, hydroxyalkyl having 1 – 4 carbon atoms, alkyl having 1 – 4 carbon atoms and halogen, with the proviso that the number of residues R₁, R₂, R₃, R₄, R₅ and R₆ which are halogen ranges from 1 to 5.

